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Contents

v	<i>Authors</i>
vii	<i>Conference Committee</i>

3D METROLOGY APPLICATIONS

10991 02	Wide-field 3D imaging with an LED pattern projector for accurate skin feature measurements via Fourier transform profilometry (Rising Researcher Paper) [10991-1]
10991 04	Toward an automatic 3D measurement of skin wheals from skin prick tests (Invited Paper) [10991-3]
10991 05	In-situ measurement of aspherics with sub-aperture deflectometry for precision optical manufacturing (Invited Paper) [10991-4]

METROLOGY ANALYSIS I

10991 06	Sources of errors in structured light 3D scanners (Invited Paper) [10991-5]
10991 08	Motion-induced error reduction for phase shifting profilometry using double-shot-in-single-illumination technique [10991-7]
10991 09	Efficient correspondence search algorithm for GOBO projection-based real-time 3D measurement [10991-8]

METROLOGY ANALYSIS II

10991 0A	Three-dimensional shape measurement of specular object with discontinuous surfaces by direct phase measuring deflectometry (Invited Paper) [10991-9]
10991 0D	Bi-frequency temporal phase unwrapping using deep learning [10991-12]
10991 0F	Fitting contrast by least square method for phase-shifting interferometry of unknown and arbitrary phase-steps under high non-uniform illumination [10991-14]

3D METHODS I

- 10991 OH **Single-shot 3D shape reconstruction using multi-wavelength pattern projection** [10991-15]
- 10991 OI **Real-time high dynamic range 3D scanning with RGB camera** [10991-16]
- 10991 OJ **Pattern projection in the short-wave infrared (SWIR): accurate, eye-safe 3D shape measurement (Rising Researcher Paper)** [10991-17]
- 10991 OK **Large-volume NIR pattern projection sensor for continuous low-latency 3D measurements** [10991-18]
- 10991 OL **Methods for addressing multiple reflections in a structured light profiler** [10991-19]

3D METHODS II

- 10991 OM **High dynamic range 3D shape measurement based on multispectral imaging (Invited Paper)** [10991-20]
- 10991 ON **Multi-axis heterodyne interferometric for simultaneous observation of 5 degrees of freedom using a single beam** [10991-21]
- 10991 OO **Simultaneous high-speed measurement of 3D surface shape and temperature** [10991-22]

METROLOGY FOR ADDITIVE MANUFACTURING I

- 10991 OR **X-ray computed tomography instrument performance evaluation: Detecting geometry errors using a calibrated artifact** [10991-25]
- 10991 OS **3D on machine metrology for conformal printing of conductors and dielectrics onto complex 3D surfaces** [10991-26]

METROLOGY FOR ADDITIVE MANUFACTURING: CRITICAL TECHNOLOGY REVIEW

- 10991 OU **Evaluation of technologies for autonomous visual inspection of additive manufacturing (AM) (Invited Paper)** [10991-28]
- 10991 OX **Process monitoring strategy for metal additive using off-the-shelf metrology (Invited Paper)** [10991-31]

Authors

Numbers in the index correspond to the last two digits of the seven-digit citation identifier (CID) article numbering system used in Proceedings of SPIE. The first five digits reflect the volume number. Base 36 numbering is employed for the last two digits and indicates the order of articles within the volume. Numbers start with 00, 01, 02, 03, 04, 05, 06, 07, 08, 09, 0A, 0B...0Z, followed by 10-1Z, 20-2Z, etc.

Alberts, Gabriel, 0R
Aloisi, Valentina, 0R
Altamar-Mercado, Hernando, 04
Barcelata-Pinzón, A., 0F
Brahm, Anika, 0H
Bräuer-Burchardt, Christian, 0K
Breitbarth, Andreas, 0H
Centamore, Allison A., 0U
Chen, Qian, 0D
Chiu, Harry, 0S
Dietrich, Patrick, 09, 0O
Feng, Shijie, 0D
Finney, Greg A., 0U
Gao, Nan, 0A
Gebhart, Ingo, 0O
Grosmann, Pascal, 09
Harding, Kevin, 0L, 0S, 0X
Heinze, Matthias, 0K
Heist, Stefan, 09, 0J, 0O
Kim, Felix, 0R
Kodgirwar, Shantanu P., 0K
Kühmstedt, Peter, 09, 0J, 0K, 0O
Landmann, Martin, 09, 0J, 0O
Lee, Vincent, 0R
Li, Beiwen, 08, 0I, 0M
Li, Shaoliang, 05
Libbey, Brad, 0N
Liu, Xiaohong, 0A
Lutzke, Peter, 09, 0O
Marrugo, Andrés G., 02, 04
Marrugo, Javier, 04
Meneses, Jaime, 02, 04
Meneses-Fabian, C., 0F
Munkelt, Christoph, 0K
Muralikrishnan, Bala, 06, 0R
Nehmetallah, George, 0N
Niu, Zhenqi, 05
Notni, Gunther, 09, 0H, 0J, 0K, 0O
Perea, James, 0N
Persons, Christopher M., 0U
Phillips, Steve, 0R
Pineda, Jesus, 04
Rachakonda, Prem, 06
Ramamurthy, Rajesh, 0S
Ren, Wei, 0R
Romero, Lenny A., 02, 04
Rosenberger, Maik, 0H
Sawyer, Daniel, 06
Shilling, Meghan, 0R
Steglich, Martin, 0J
Suresh, Vignesh, 08, 0M
Tait, Robert, 0S
Tao, Tianyang, 0D
Templin, Joachim, 0O
Trevithick, Caleb P. M., 0U
Vargas, Raúl, 04
Wang, Yajun, 08, 0I, 0M
Whitten, Jacob R., 0U
Xu, Xueyang, 05
Yin, Wei, 0D
Zhang, Chen, 0H
Zhang, Xiangchao, 05
Zhang, Yueqian, 0J
Zhang, Zonghua, 0A
Zhao, Wanliang, 05
Zheng, Yi, 0I, 0M
Zuo, Chao, 0D

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- 1 3D Metrology Applications
Song Zhang, Purdue University (United States)
- 2 Metrology Analysis I
Chao Zuo, Nanjing University of Science and Technology (China)
- 3 Metrology Analysis II
Yajun Wang, Wuhan University (China)
- 4 3D Methods I
Martin Landmann, Friedrich-Schiller-Universität Jena (Germany)
- 5 3D Methods II
Stefan Heist, Friedrich-Schiller-Universität Jena (Germany)
- 6 3D Methods III
Kevin G. Harding, Optical Metrology Solutions (United States)
- 7 Metrology for Additive Manufacturing I
Kevin G. Harding, Optical Metrology Solutions (United States)
- 8 Metrology for Additive Manufacturing: Critical Technology Review
Kevin G. Harding, Optical Metrology Solutions (United States)